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Eindhoven (NL). **LOCH, Rolf, A.** [NL/NL]; c/o Prof. Holstlaan 6, NL-5656 AA Eindhoven (NL).

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(74) Agents: **UITTENBOGAARD, Frank** et al.; Prof. Holstlaan 6, NL-5656 AA Eindhoven (NL).

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(71) Applicant (*for all designated States except US*): **KONINKLIJKE PHILIPS ELECTRONICS N.V.** [NL/NL]; Groenewoudseweg 1, NL-5621 BA Eindhoven (NL).

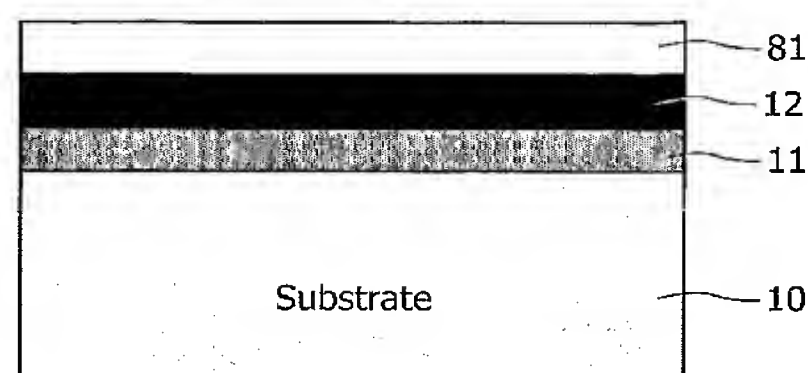
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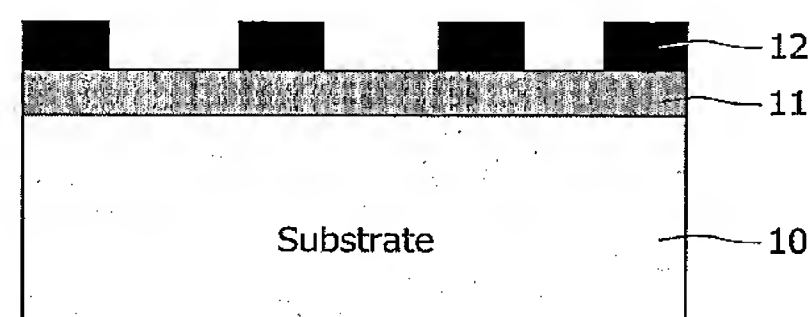
(75) Inventors/Applicants (*for US only*): **MEINDERS, Erwin, R.** [NL/NL]; c/o Prof. Holstlaan 6, NL-5656 AA

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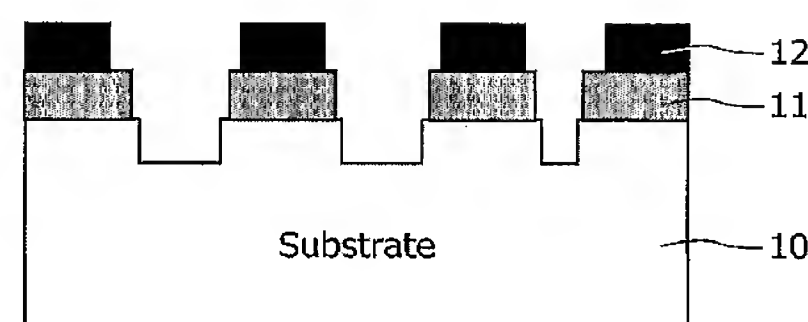
(54) Title: OPTICAL MASTER SUBSTRATE WITH MASK LAYER AND METHOD TO MANUFACTURE HIGH-DENSITY RELIEF STRUCTURE



a



b



c

(57) Abstract: The invention relates to a master substrate, a method for making a high-density relief structure, and optical discs replicated with the high-density relief structure, the master substrate comprising a substrate layer (10) and a recording stack deposited on the substrate layer, the recording stack comprising: - a mask layer (12) - an interface layer (11) sandwiched between said mask layer and the substrate, said mask layer comprising a recording material for forming marks and spaces representing an encoded data pattern, said forming of marks by thermal alteration by a focused laser beam and said marks having a different phase than the unrecorded material. A very high-density relief structure is achieved.



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